

### **REMARKS**

Claims 1, 2, 5-8 and 12-16 remain pending in the present application. Applicant would like to thank the Examiner for the thorough consideration given to the present application and the courtesies extended to applicant's representative during a telephone interview on February 12, 2003. During that interview, the Examiner indicated that the arguments as set forth below overcome the outstanding rejection of the pending claims. Therefore, the Examiner is respectfully requested to reconsider and withdraw his rejections in view of the arguments as set forth below.

### **REJECTIONS UNDER 35 USC §103**

Claims 1, 2, 5-8 and 12-16 stand rejected under 35 USC §103(a) as being unpatentable over U.S. Patent No. 5,970,384 (Yamazaki) in view of the U.S. Patent Publication Nos. US 2002/0037442 (Grill) and US 2002/0034863 (Yamazaki). Applicant respectfully traverses this rejection.

Yamazaki is directed generally to a method of heat treating silicon oxide films by irradiating ultra-violet light. As noted by the Examiner, Yamazaki fails to teach or suggest setting the substrate temperature at no higher than 100 degrees Celsius and heat treating the gate insulating film in an atmosphere containing water.

The Examiner then relies on Grill to teach setting the substrate temperature at no higher than 100 degrees Celsius. In particular, the Examiner points to the deposition of multiphase film 38. However, Applicant notes that the multiphase

film 38 is not deposited on substrate 32. Referring to Figure 6, an insulating material layer 34 is formed between the multiphase film 38 and the substrate 32.

Therefore, Applicant asserts that the teachings of Grill are not relevant to Applicant's claimed invention.

On the contrary, Applicant's claimed invention is directed generally to a method for fabricating a field-effect transistor. Of interest, Claim 1 recites "setting the substrate temperature at no higher than 100 C" in combination with the other elements recited in the claim. For reasons set forth above and in our previous response, it is respectfully submitted that Claim 1 defines patentable subject matter over the relied upon references.

Applicant notes that other pending claims recite similar subject matter, and thus should be allowable, along with claims depending therefrom, for the same reasons as Claim 1. Accordingly, Applicant respectfully requests reconsideration and withdrawal of this rejection.

### **CONCLUSION**

All of the stated grounds for rejection have been properly traversed, accommodated, or rendered moot. Applicant therefore respectfully requests that the Examiner reconsider all presently outstanding rejections and further requests that they be withdrawn. Accordingly, it is believed that a full and complete response has been made to the outstanding Office Action and, as such, the

present application is in condition for allowance. If the Examiner believes that personal communication will expedite prosecution of this application, he is invited to telephone the undersigned at (248) 641-1600.

Prompt and favorable consideration of this response is respectfully requested.

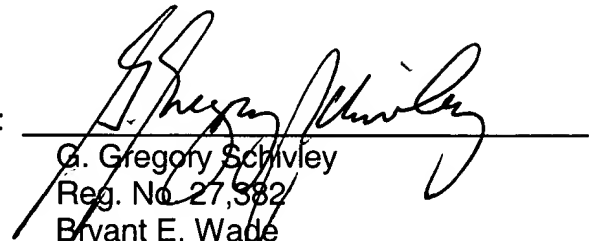
Respectfully submitted,

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